

## Refine Search

### Search Results -

Terms	Documents
L7 and L3	41

Database:

US Pre-Grant Publication Full-Text Database  
 US Patents Full-Text Database  
 US OCR Full-Text Database  
 EPO Abstracts Database  
 JPO Abstracts Database  
 Derwent World Patents Index  
 IBM Technical Disclosure Bulletins

Search:






### Search History

DATE: **Wednesday, March 17, 2004**    [Printable Copy](#)    [Create Case](#)

**Set Name Query**  
side by side

**Hit Count Set Name**  
result set

*DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ*

<u>L8</u>	L7 and l3	41	<u>L8</u>
<u>L7</u>	L6 or l5 or l6	86871	<u>L7</u>
<u>L6</u>	55/\$.ccls.	44515	<u>L6</u>
<u>L5</u>	454/\$.ccls.	44708	<u>L5</u>
<u>L4</u>	438/\$.ccls.	152613	<u>L4</u>
<u>L3</u>	L2 and (air near4 (ducts or sections))	125	<u>L3</u>
<u>L2</u>	L1 and (second or post) near5 (clean\$ or ventilat\$)	803	<u>L2</u>
<u>L1</u>	clean room and semiconductor	8480	<u>L1</u>

END OF SEARCH HISTORY